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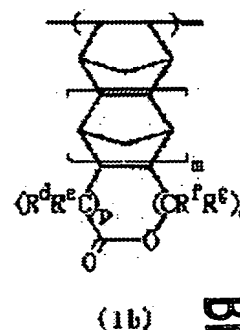
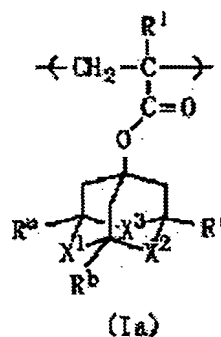
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(54) POLYMER COMPOUND FOR PHOTORESIST AND PHOTORESIST RESIN COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a polymer compound for photoresist excellent in adhesiveness to a substrate and capable of forming fine patterns in good accuracy.

SOLUTION: This polymer compound for photoresist contains at least one species of monomer units selected from monomer units expressed by formula (Ia) and (Ib) (wherein R¹, R_a, R_b, R_c, R_d, R_e, and R_g are each the same or different and express H or methyl; X₁, X₂, and X₃ are each -CH₂- or -CO-O- and at least one of them expresses -CO-O-; m, p and q are each an integer of 0-2).



LEGAL STATUS

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